

Composition Fluctuation Intensity Effect on the Stability in Polymer Films

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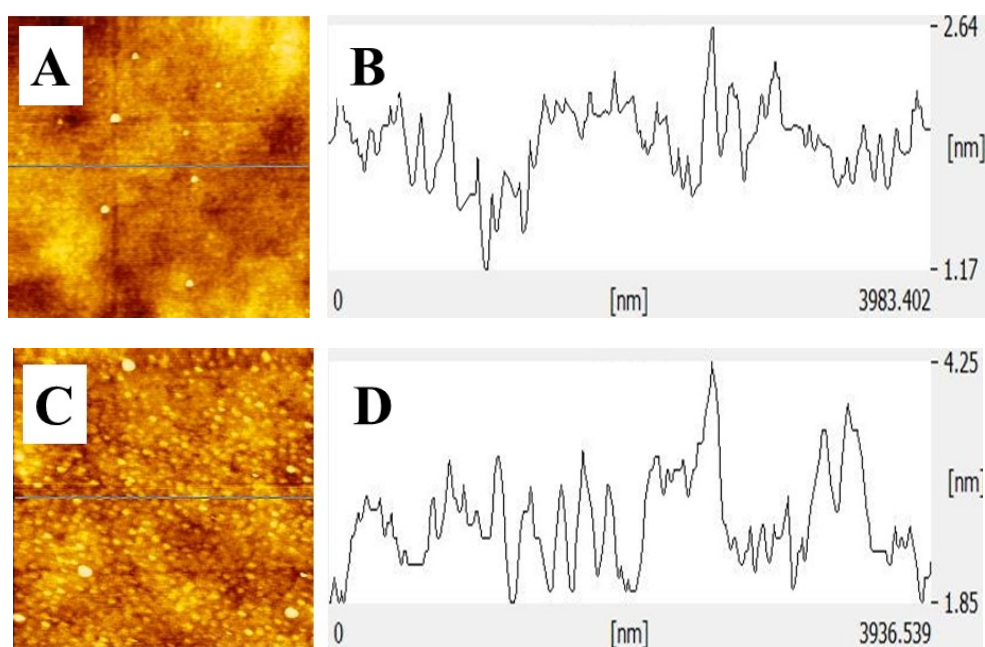


Figure S1, AFM topography images (A and C, corresponding to Figure 2A4 and Figure 2B4, respectively) and line-cut profiles of them (B and D).

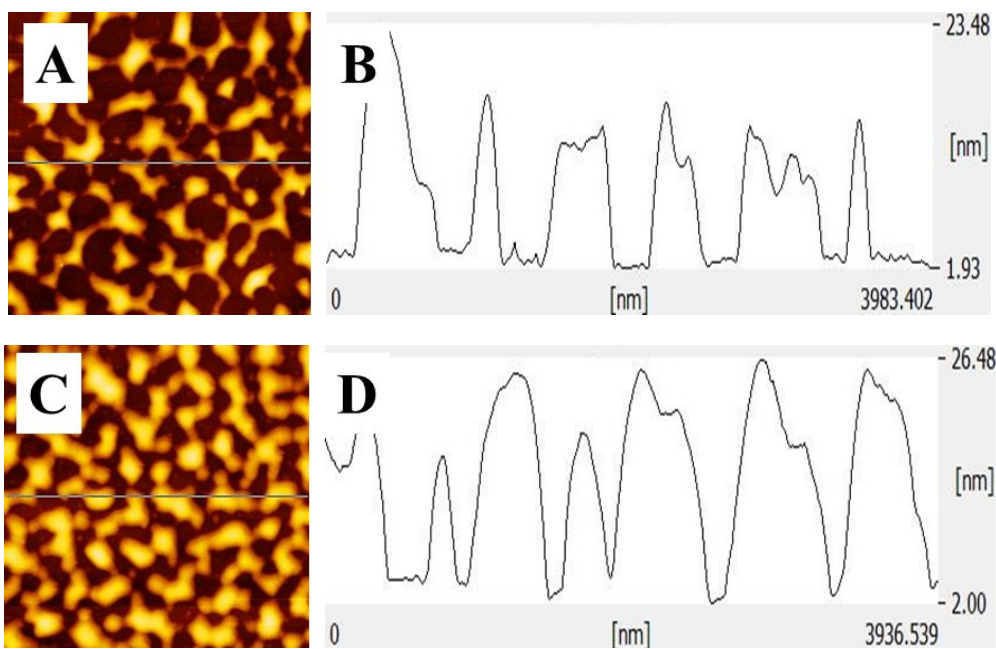


Figure S2, AFM topography images (A and C, corresponding to Figure 3A4 and Figure 3B4, respectively) and line-cut profiles of them (B and D).

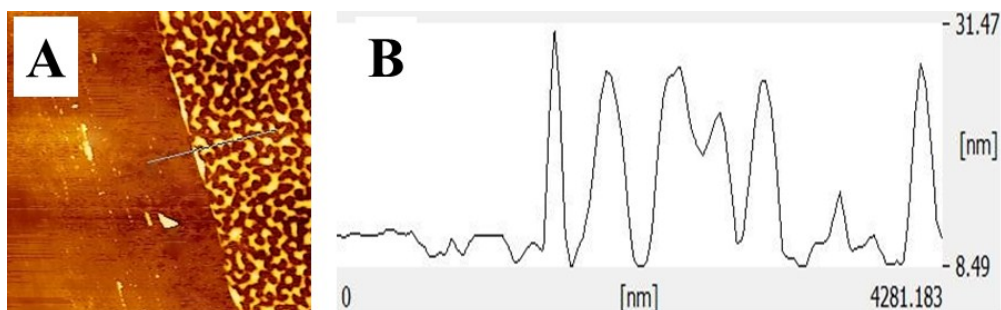


Figure S3, AFM topography image (A) of the scratched specimen and line-cut profile of the indicated position (B). The heights of the scratched and un-scratched area are nearly equal, suggesting that the substrate has been exposed to air.

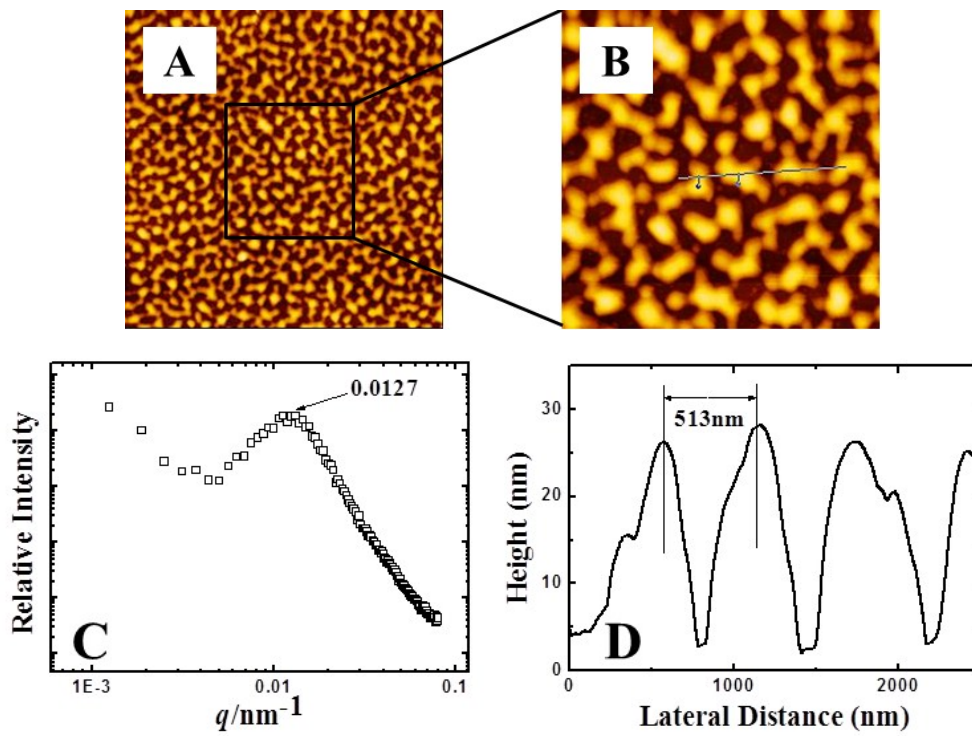


Figure s4, Topography images for SAN98 at 145°C for 12h, (A) $10 \times 10 \mu\text{m}^2$, (B) $4 \times 4 \mu\text{m}^2$, (C) Fast Fourier transition (FFT) of image fig.s4(A), (D) The line-cut profiles on image fig.s4(B) on the indicated position.